

L Number	Hits	Search Text	DB	Time stamp
2	0	removal same 'polymer residue' same 'fluorine' and @ad<=19990219 and 'ultraviolet' and 'ammonia'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 10:54
3	0	'polymer residue' same 'fluorine' and @ad<=19990219 and 'ultraviolet' and 'ammonia'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 10:54
4	10	'polymer residue' and 'fluorine' and @ad<=19990219 and 'ultraviolet' and 'ammonia'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 10:55
11	162	'fluorine containing polymer' and @ad<=19990219 and 'ultraviolet' and 'ammonia'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 11:24
13	1	'cleaning' with 'fluorine containing polymer' and @ad<=19990219 and 'ultraviolet' and 'ammonia'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 11:25
14	2	("6272768").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 11:42
15	1		USPAT	2002/11/12 11:45
16	1		USPAT	2002/11/12 11:45
17	1		USPAT	2002/11/12 11:45
18	1		USPAT	2002/11/12 11:46
19	1		USPAT	2002/11/12 11:46
20	1		USPAT	2002/11/12 11:46
21	1		USPAT	2002/11/12 11:46
22	124	@ad<=19990219 and 'ultraviolet' same 'simultaneous' and 'ammonia'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 11:50
23	1	@ad<=19990219 and 'substrate cleaning' and 'ultraviolet' same 'simultaneous' and 'ammonia'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 11:53
25	4	@ad<=19990219 and 'semiconductor substrate' and 'ultraviolet' same 'simultaneous' and 'ammonia'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 12:07
27	5	@ad<=19990219 and 'semiconductor substrate' same 'cleaning' and 'ultraviolet' same 'ammonia'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 12:12
29	8	@ad<=19990219 and 'substrate cleaning' and 'ultraviolet' same 'ammonia'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 12:20
30	184	(438/715).ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 13:44





	6	((134/1-4).ccls. and @ad<=19990219) and 'ultraviolet' and 'ammonia gas'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/10 14:07
	11	((134/1-4).ccls. and @ad<=19990219) and 'fluorine residue'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/10 14:06
	161	(438/715).ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/11/12 13:43
	3	((438/715).ccls.) and @ad<19990219 and 'volatilize'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/10 14:12
	7	(("5129958") or ("5935340") or ("5207836")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/10 14:16
	714	'fluorine' with 'photoresist'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/10 14:19
	514	('fluorine' with 'photoresist') and @ad<=19990219	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/10 14:18
	0	'photoresist containing fluorine' and @ad<=1999019	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/10 14:19
	188	'ashing photoresist' and @ad<=19990219	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/10 15:52
	65	('ashing photoresist' and @ad<=19990219) and 'ultraviolet'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/10 15:52
	0	(('ashing photoresist' and @ad<=19990219) and 'ultraviolet') and 'ammonia'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/10 15:53
	0	(('ashing photoresist' and @ad<=19990219) and 'ultraviolet') and 'NH3'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/10 15:53
	0	'cleaning photoresist' with 'flourine containing' and @ad<=19990219	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/11/12 09:25
	0	removal adj 'flourine containing residue' and @ad<=19990219	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/11/12 09:17

-	0	removal adj 'flourine containing' and @ad<=19990219	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 09:18
-	71	'removal' and 'flourine containing' and @ad<=19990219	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 09:18
-	0	('cleaning process' and @ad<=19990219 and 'fluorine containing') and 'ultraviolet' near 'simultaneous'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 09:21
-	8	@ad<=19990219 and 'fluorine containing residue'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 09:21
-	529	'organic photoresist' and @ad<=19990219	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 09:50
-	47	('organic photoresist' and @ad<=19990219 ) and 'ultraviolet' and 'simultaneous' and 'gas'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 09:54
-	512982	cleaning or removal same 'organic photoresist' and @ad<=19990219	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 09:42
-	28	cleaning same 'organic photoresist' and @ad<=19990219	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 09:54
-	11	'organic photoresist' with 'fluorine' and @ad<=19990219	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 10:38
-	1483	(cleaning or removal same 'organic photoresist' and @ad<=19990219 ) and 'ultraviolet' and 'simultaneous'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 09:57
-	437	((cleaning or removal same 'organic photoresist' and @ad<=19990219 ) and 'ultraviolet' and 'simultaneous') and 'ammonia'	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 11:48
-	2	("6272768").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/11/12 10:15